

ICMCT-2014 [10th – 12th March 2014]
International Conference on Materials and Characterization Techniques

Structural, optical and magnetic properties of Ni- doped SnO₂ thin films prepared by flash evaporation technique

M. Kuppan¹, S. Kaleemulla^{1*}, N. MadhusudhanaRao¹, N. SaiKrishna¹,
M. RiganaBegam¹, D. SreekanthaReddy²

¹Thin Films Laboratory, School of Advanced Sciences, VIT University,
Vellore 632014, Tamilnadu, India

²Department of Physics and Sungkyunkwan Advanced Institute of Nanotechnology
(SAINT), Sungkyunkwan University, Suwon 440746, Korea

*Corres. author: skaleemulla@gmail.com

Abstract: Nickel doped SnO₂ thin films at different Ni doping concentrations were prepared using flash evaporation technique. The effect of Ni doping concentration on structural, optical and magnetic properties of the thin films was studied. X- ray diffraction studies revealed that all the Ni doped SnO₂ thin films were in tetragonal structure. No traces of impurities were found even at higher Ni (15 at.%) doping level. The optical band gap of the films increased with the increase of Ni doping level from 3 at.% to 15 at.%. All the Ni doped SnO₂ thin films exhibited ferromagnetism at room temperature. The saturation magnetic moment (Ms) increased with increase of Ni doping level from 3 at.% to 7 at.% and then it decreased by further increase of Ni doping levels.

Keywords: Oxide thin film, Flash evaporation, Ferromagnetism.

Introduction

Recently transparent conducting Oxides (TCO's) have drawn much interest in the field of optoelectronics [1]. Transparent conducting oxides are the material which exhibit higher optical transmittance in visible region, low sheet resistance and higher electrical conductivity. Among the various TCO's such as ZnO, In₂O₃, CdO, TiO₂ and SnO₂[2], SnO₂ is the most promising candidate for the development of transparent conductive ferromagnetic material. SnO₂ is an rutile tetragonal structure with oxygen deficient n- type degenerate semiconductor with wide band gap of 3.6eV. Its high optical transparency and electrical conductivity leads to very appealing applications in spintronics devices. In the present work, Sn_{1-x}Ni_xO₂ thin films were prepared using flash evaporation method. The influence of doping level on structural, optical and magnetic properties of Ni doped SnO₂ thin films had been studied.

Experimental procedure:

Ni doped SnO₂ thin films were prepared on glass substrate by convenient flash evaporation technique using the 12" vacuum coating unit (model:12A4D). Through which the target materials NiO and SnO₂ are loaded systematically. The source materials were prepared using standard solid state reaction method. Molybdenum

boats was used to vaporize the material. The base and working pressure inside the chamber was 1×10^{-6} mbar and 3×10^{-6} mbar which could be measured using pirani and penning gauges. The substrate temperature set to be as 573 K. And the as deposited films were annealed at 773 K in air ambience for 2 hrs. The structural, optical and magnetic properties of the annealed thin films were characterized by Bruker D-8 Advance X-ray diffractometer ($\text{Cu K}\alpha = 1.5406 \text{ \AA}$), optical transmittance spectra were recorded using UV-Vis spectrophotometer (JASCO-V-670) and the magnetic hysteresis studies were done by using vibrating sample magnetometer respectively.

Results and Discussion

Structural property of un doped and Ni doped SnO_2 thin films

Fig.1 shows the XRD diffraction patterns $\text{Sn}_{1-x}\text{Ni}_x\text{O}_2$ thin films ($x = 0$ to 0.15 at.%). The films annealed at 773 K were polycrystalline in nature. The diffraction peaks of (110), (101) and (211) were exactly coinciding with rutile structure of SnO_2 . No traces of impurity of NiO, Ni peaks were not found even with higher doping concentrations.

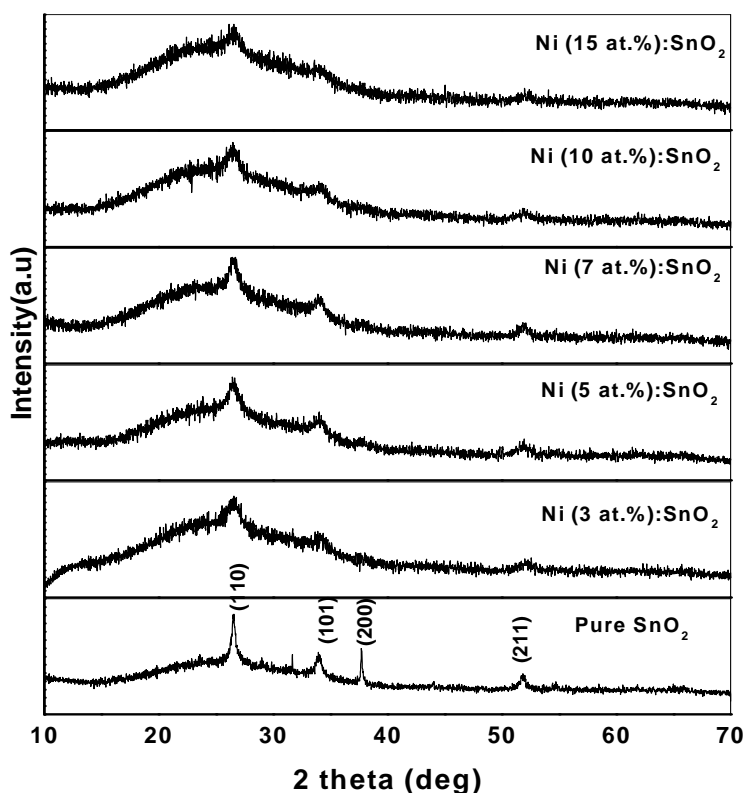


Fig.1 XRD diffraction patterns of $\text{Sn}_{1-x}\text{Ni}_x\text{O}_2$ thin films ($x = 0$ to 15 at.%)

The crystallite size of $\text{Sn}_{1-x}\text{Ni}_x\text{O}_2$ thin films ($x = 0$ to 0.15 at.%) was calculated using Scherer's relation. The crystallite size of films varied from 21 to 10 nm with increase of doping concentration similar to Dalui *et al* [4]. The lattice parameter of these films was also varied. This implies that Ni has incorporated in to host SnO_2 lattice.

Optical properties of Ni doped SnO_2 thinfilms

The optical transmittance spectra of the Ni doped SnO_2 thin films were recorded from 200 nm to 2500 nm wavelength, which is not shown here. From the figure it was noticeable that optical transmittance was higher for pure SnO_2 annealed films (72%) where as after doping with Ni impurity in to the host exhibited poor in transparency. The optical band gap (E_g) of the films were determined by plotting $(\alpha h\nu)^2$ versus the photon energy ($h\nu$) and extrapolating the linear region of the plots to zero ($\alpha=0$). The band gap decreased (3.95 -3.11 eV) with Ni doping concentration which is not shown here, similar to Ahmed *et.al* [5]. The increase or decrease in the band gap energy may be due to accumulation of donor or narrowing effects, energy levels of transition metal ions in the actual band gap of SnO_2 .

Magnetic property of Ni doped SnO₂ thinfilms

Fig.2 shows the M-H curves for Sn_{1-x}Ni_xO₂ thin films with different Ni doping concentrations from x = 3 to 15 at.%. The diamagnetic nature becomes ferromagnetic by adding a little amount of oxide magnetic impurity. This may be due to oxygen vacancy and substitution of Sn atom by Ni atom interstitially. In other words the oxygen vacancy near the impurity plays vital role in mediating the ferromagnetism in this system at room temperature. The saturation magnetization increased with increase of Ni doping concentration. However on continually increase of Ni doping for higher concentration the saturation magnetization turns to decrease gradually. Thus we strongly feels that the oxygen vacancy and or defects in the Ni doped SnO₂system, which are in good agreement with the model proposed by Coey et al.[3] The maximum magnetic saturation (ms) 113.76x10⁻⁶emu, magnetic retentivity (mr) 9.501 and coercivity (Hci) 97.715 were obtained for Ni (5 at.%) doped SnO₂thin films.

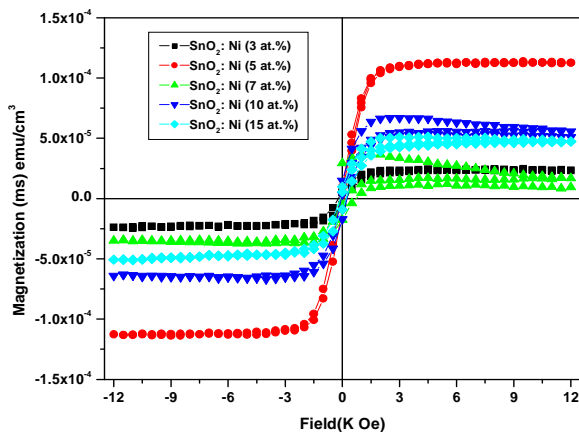


Fig. 2 M-H curves for Sn_{1-x}Ni_xO₂ thin films (x = 3 to 15 at.%).

Conclusion

Ni doped SnO₂ thin films were successfully deposited on glass substrates using flash evaporation technique. The films annealed at 773 K exhibited tetragonal rutile structure of SnO₂. From the optical transmittance it was revealed that the transparency and band gap decreased with doping concentration. Ferromagnetic behavior of Ni doped SnO₂ thin films were obtained at room temperature. The maximum magnetic saturation (ms) were obtained for Ni (5% at.%) doped SnO₂ thin films.

References

1. Peeloers H. Kioupakis E. Van de walle C.G, Fundamental limits on optical transparency of transparent conducting oxides: Free carrier absorption in SnO₂ .Appl.Phy.Lett,100, 011914 (2012).
2. Cathleen A. Hoel T. Thomas O. Mason, Transparent conducting oxides in the ZnO-In₂O₃-SnO₂ system,Chem.matter.22, 3569-3579 (2010).
3. Coey J.M.D. Venkatesan M. Fitzgerald C.B. Donor impurity band exchange in dilute ferromagnetic oxides, Nature material, Vol .4, 173 - 179 (2005)
4. Dalui S. Rout S. Silvestre A.J. Lavareda G. Pereira L.C.J., Structural, electrical and magnetic studies of Co: SnO₂ and (Co,Mo): SnO₂ film prepared by pulsed laser deposition, Appl. Surf.Sci, 24798 (2013).
5. Ahmed A.S. Azam A. Shafeeque M. Chaman M. Tabassum S., Temperature dependent structural and optical properties of tin oxide nanoparticles, Journl.phy.chem.sol, 73,943, (2012).
